

Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it displays a valid OMB control number.

Substitute for form 1449A/PTO

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(use as many sheets as necessary)

Sheet

1

of

2

Complete if Known

Application Number

09/699,614

Filing Date

10/30/2000

First Named Inventor

Silver

Group Art Unit

2621

Examiner Name

Not Known

Attorney Docket Number

C00-057Technology Center 2600

U.S. PATENT DOCUMENTS

[illegible]

FOREIGN PATENT DOCUMENTS

[illegible]

**Examiner
Signature**

Date
Considered

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹Unique citation designation number. ²See attached Kinds of U.S. Patent Documents. ³Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶Applicant is to place a check mark here if English language Translation is attached.

Burden Hour Statement: This form is estimated to take 2.0 hours to complete. Time will vary depending upon the needs of the individual case. Any comments on the amount of time you are required to complete this form should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, Washington, DC 20231. **DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO:** Assistant Commissioner for Patents, Washington, DC 20231.

Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it displays a valid OMB control number.

Substitute for form 1449B/PTO

**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

(use as many sheets as necessary)

Sheet

2

of

2

Complete if Known

Application Number 09/699,614

Filing Date 10/30/2000

First Named Inventor Silver

Group Art Unit 2854

Examiner Name Not Known

Attorney Docket Number C00-057

RECEIVED

OCT 23 2001

Technology Center 2600

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Citeq No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
BL		KLA-TENCOR, INC., Candidate Alignment Target For Wafer, 1997	
		DAVID I. HAVERLOCK, Geometric Precision in Noise-Free Digital Images, IEEE Transactions on Pattern Analysis and Machine Intelligence, VOL. II No 10. October 1989	
		JOHN W. HILL, Machine Intelligence Research Applied To Industrial Automation, National Technical Information Service, U.S. Department of Commerce, November 1980	
		CHINMOY B. BOSE AND ISREAL AMIR, Design of Fiducials for accurate Registration Using Machine Visions, IEEE Transaction on Pattern Analysis and Machine Intelligence, VOL. 12 No. 12, December 1990	
		LAWRENCE O'GORMAN, Subpixel Precision of Straight-Edged Shapes for Registration and Measurement, IEEE Transactions on Pattern Analysis and Machine Intelligence, VOL. 18, No. 7 1996	
		H.F. GILLESPIE AND J.E. MARTIN, Optimization of Optical Alignment Marks Through Circuit Design Rule Consideration, Rockwell International, Newport Beach, CA, 1978	
		NEAL T. SULLIVAN, Semiconductor Pattern Overlay, Digital Equipment Corp., Advanced Semiconductor Development	
		HIDEKI INA, KOICHI SENTOKU AND TAKAHIRO MATSUMOTO (Nanotechnology research Center) - HIROAKI SUMITANI AND MUNEO YOSHIDA (Advanced Technology R&D Center, Alignment Mark Optimization to Reduce Tool and Wafer Induced Shift for XRA-1000	
		W. MAKOUS, Optimal Patterns For Alignment, Applied Optics Vol. 13, No. 3, March 1974	
		EGIL D. CASTEL and NADER SHAMMA, Design and Optimization of Site-By-Site Alignment Marks for a Single Polysilicon Bipolar Process, National Semiconductor Corporation, Elsevier Science Publishers B.V.	
BL		ALFRED M. BRUCKSTEIN, LARRY O'GORMAN AND ALON ORLITSKY, Design of Shapes for Precise Image Registration, IEEE Transactions on Information Theory, VOL. 44, No. 7, November 1998	

Examiner
Signature

Bresch

Date
Considered

10/22/03

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹Unique citation designation number. ²Applicant is to place a check mark here if English language Translation is attached.

Burden Hour Statement: This form is estimated to take 2.0 hours to complete. Time will vary depending upon the needs of the individual case. Any comments on the amount of time you are required to complete this form should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, Washington, DC 20231. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Assistant Commissioner for Patents, Washington, DC 20231